Journal Leadership in Transition

This issue of the *AIChE Journal* marks the transition in Editorship from Professor and Dean Matthew V. Tirrell of the University of California, Santa Barbara, to Professor Stanley Sandler of the University of Delaware. This is a very significant event, as in its nearly 50-year history, the *Journal* has seen only six editors!

In the past 15 years, the *AIChE Journal* has become firmly established as the flagship archival journal of the chemical engineering profession, publishing the most significant research results from all areas of chemical engineering. Under the six-year leadership of Professor Morton Denn, the 4th Editor, the *Journal* grew in editorial pages to become a monthly, achieved a publication time of less than one year between submission and publication, and broadened its scope to include contributions reporting innovative research in emerging areas of chemical engineering endeavor. In his nine years as Editor, Professor Tirrell has solidified the preeminence of the *Journal* in the global chemical engineering profession, has introduced the online version of the *Journal*, has overseen the introduction of the new *Perspectives* section and the new cover design, sustained the annual submission rate of new contributions to nearly 600 papers, has achieved a stable acceptance rate of 40–50%, and has consistently maintained the publication time to 10 months or less. Most importantly, he has promoted the inclusion of new topics of chemical engineering research interest by instituting a system of Area Associate Editors, consisting of outstanding academic and industrial researchers in highly active and relevant technical areas. This spirit of technical inclusivity has been and will continue to be important to the chemical engineering profession as it explores new domains and exploits the explosion of scientific discoveries in the natural and life sciences. AIChE and indeed the international chemical engineering research community owe Professor Tirrell a great debt of thanks for his exemplary stewardship of our highly prized *Journal*.

At the end of 1999, upon indication from Professor Tirrell of his desire to retire from the Editorship as a result of the press of responsibilities he faced as Dean of Engineering, a search committee was formed to identify his successor. Professor Ronald W. Rousseau accepted the chairmanship of a broad-based committee consisting of Dr. Rakesh Agrawal, Air Products; Prof. Mark Davis, California Institute of Technology, Prof. Pablo Debenedetti, Princeton University, Dr. Sangtae Kim, Eli Lilly; Prof. Robert Langer, MIT; Prof. Rex Reklaitis, Purdue University; and Prof. Warren Seider, University of Pennsylvania. As the result of a call for nominations widely disseminated to the chemical engineering community, an initial pool of over 50 very capable candidates was developed. On the basis of a careful screening process, Professor Stanley Sandler emerged as the candidate of choice. Fortunately, he agreed to accept the Editorship of the *Journal* and thus becomes the 6th Editor. Professor Rousseau should be acknowledged for his highly effective and professional leadership in the successful completion of this search process.

Our new Editor assumes the helm of a well-tuned and managed ship, but will face the challenge of steering that ship into the uncertain waters of further dramatic changes in the nature of technical publishing, spanning all aspects of manuscript preparation, editorial handling, review, publication, and dissemination brought about by Internet developments. He will need all our help to overcome the winds which put us at risk of dissipating the core of the profession as research interests drive the chemical engineering community to explore ever more distant frontiers. Professor Sandler has the breadth of vision, scientific acumen and standards, and high credibility to bring the *Journal* to even greater prominence in this challenging environment. We wish him success and satisfaction in the coming years.

G. V. Rex Reklaitis
Chair, Publication Committee